

## Refine Search

### Search Results -

Terms	Documents
aluminum adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	0

Database:

US Pre-Grant Publication Full-Text Database  
 US Patents Full-Text Database  
 US OCR Full-Text Database  
 EPO Abstracts Database  
 JPO Abstracts Database  
 Derwent World Patents Index  
 IBM Technical Disclosure Bulletins

Search:

L19

Refine Search

Recall Text

Clear

Interrupt

### Search History

 DATE: Thursday, August 19, 2004    [Printable Copy](#)    [Create Case](#)

<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
	DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ		
L19	aluminum adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	0	L19
L18	ammonium adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	6	L18
L17	(hydroxylamine adj nitrate or hydrazine) and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	0	L17
	DB=PGPB,USPT; PLUR=YES; OP=ADJ		
L16	L14 and (polish or polishing) adj stop	0	L16

<u>L15</u>	L14 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	1	<u>L15</u>
<u>L14</u>	L13 and (hydroxylamine or hydroxyl adj amine or ammonium adj nitrate or aluminum adj nitrate or hydrazine)	14	<u>L14</u>
<u>L13</u>	L10 or L11 or L12	38	<u>L13</u>
<u>L12</u>	20020062600 or 20010037821	2	<u>L12</u>
<u>L11</u>	US-6149696-\$.DID. OR US-6299795-\$.DID. OR US-6117775-\$.DID. OR US-6461227-\$.DID. US-6156661-\$.DID. OR US-6140239-\$.DID. OR US-6117733-\$.DID. OR US-6063306-\$.DID. OR US-5954997-\$.DID. OR US-5981454-\$.DID. OR US-5899740-\$.DID. OR US-5897375-\$.DID. OR US-5863307-\$.DID. OR US-5858813-\$.DID. OR US-5840629-\$.DID. OR US-5780358-\$.DID. OR US-5770517-\$.DID. OR US-5735963-\$.DID. OR US-5614444-\$.DID. OR US-5575837-\$.DID. OR US-5527423-\$.DID. OR US-5354490-\$.DID. OR US-5340370-\$.DID. OR US-5225034-\$.DID. OR US-4724042-\$.DID. OR US-4556449-\$.DID. OR US-4013758-\$.DID. OR US-3592773-\$.DID. OR US-3410802-\$.DID. OR US-3385682-\$.DID. OR US-3137600-\$.DID. OR US-6293848-\$.DID. OR US-6398827-\$.DID. OR US-4959113-\$.DID. OR US-4204013-\$.DID. OR US-5281311-\$.DID.	4	<u>L11</u>
<u>L10</u>		32	<u>L10</u>
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L9</u>	L8 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	4	<u>L9</u>
<u>L8</u>	abrasive and aluminum adj nitrate and copper and (dielectric or insulating) and (tantalum or tantalum adj nitride)	49	<u>L8</u>
<u>L7</u>	abrasive and aluminum adj nitrate and copper and (dielectric or insulating) and (tantalum or tantalum adj nitride) and (polishing or polish)adj stop	0	<u>L7</u>
<u>L6</u>	abrasive and (ammonium or aluminum) adj4 nitrate and copper and dielectric and (tantalum or tantalum adj nitride) and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	34	<u>L6</u>
<u>L5</u>	L3 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	3	<u>L5</u>
<u>L4</u>	L1 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	13	<u>L4</u>
<u>L3</u>	L2 and (cmp or chemical adj mechanical adj (polish or polishing))	33	<u>L3</u>
<u>L2</u>	hydrazine and copper and dielectric and (tantalum or tantalum adj nitride) and (nitrate or nitric adj acid)	85	<u>L2</u>
<u>L1</u>	(hydroxylamine or hydroxyl adj amine) near4 nitrate and copper and dielectric and (tantalum or tantalum adj nitride) and (nitrate or nitric adj acid)	24	<u>L1</u>

END OF SEARCH HISTORY